



Vacuum Equipment - Coatings - Optics

101 Duranzo Aisle, Irvine CA 92606, USA * Phone: 1-949-394-4466 *
Phone/Fax: 1-949-451-6813 * info@vecorus.com * www.vecorus.com

Optical Coating Machines



Coating machine VU2-MM



Coating machine VU2-MI

VU2MM and **VU2MI** machines with stainless steel vacuum chamber Dia.700x700 mm are intended for optical coatings (metal, semiconductors, and dielectric; single- and multilayer AR, mirrors, achromatic, filters, transparent electro-conductive, etc.) R&D, lab, and industrial mass production by e-beam and resistive evaporation with ion-beam assistance. Coating may be deposited on glass, metal, and plastic substrates. Two cryo pumps or diffusion pump provide a vacuum chamber high vacuum pumping. The pumping and deposition runs are carried out in fully automatic (VU2-MM), semi-automatic, manual (VU2-MI) or semi-automatic (on demand) modes. Monochromatic or spectral photometer (250-1100 nm) and quartz crystal monitor are used for the deposition run monitoring.

SPECIFICATIONS

Ultimate pressure, Torr	$(4.5 - 6) \times 10^{-5}$
Pumping time to ultimate pressure, min.	30
Number/power, kW, of e-beam evaporators	2/6
Number/power, kW, of resistive evaporators	1/4
Number of ion sources/maximal ion current, A	1 / 1
Maximal weight of substrates, kg	10
Maximal temperature of substrates heating, grad C	320
Substrates rotation speed, rpm	6 - 60
Maximal number of layers to be deposited in automatic mode	32
Power, kW (depending on model)	30-40
Total floor area occupied by machine, sq.m (depending on model)	6-8
Weight, kg (depending on model)	1970, 2150

VU1100 “Optics” Optical Coating Machine



VU1100 “Optics” coating machine is intended for mass production of optical thin film coatings (metal, semiconductor, and dielectric; single- and multi-layer) by e-beam and resistive evaporation with ion-beam assistance. Stainless steel vacuum chamber Dia.1100x1000 mm is pumped down with cryo or diffusion pumps. The pumping and deposition run are carried out in fully automatic mode. The spectrophotometer (250-1100 nm) and quartz crystal monitor are used for deposition run monitoring.

SPECIFICATIONS

Ultimate pressure, Torr	6x10 ⁻⁵
Pumping time to ultimate pressure, min.	30
Number/power, kW, of e-beam evaporators	2/20
Number/power, kW, of resistive evaporators	2/6
Number of ion sources/maximal ion current, A	1 /2.5
Maximal weight of substrates, kg	50
Maximal temperature of substrates heating, grad C	320
Substrates rotation speed, rpm	6-60
Maximal number of layers to be deposited in automatic mode	32
Power, kW	75
Total floor area occupied by machine, sq.m	16
Weight, kg	2950

The coating machines and their components design and specifications are shown for reference; the real design and specifications may vary to meet customer requirements.

